



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Tadahiro OHMI, et al.

Serial No.: 09/864,376

Filed: March 25, 2001

For: PLASMA PROCESSING APPARATUS AND PLASMA  
PROCESSING METHOD

Group Art Unit: 3748

Examiner: Zervigon, Ruby

Docket No.: 107176-00007

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TC 1700

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mv

Commissioner of Patents  
Washington, DC 20231

March 13, 2003

Sir:

In response to the outstanding Office Action dated September 13, 2002, the time for reply having been duly extended until March 13, 2003, by the attached petition, please amend the application as follows:

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TC 2800 MAIL ROOM

IN THE DRAWINGS:

Attached hereto is a Request for Approval of Corrected Drawing Figures, along with a corrected Fig. 1 showing "D" added in red ink. Upon approval of the corrected Fig. 1, formal drawings will be filed in due course.

IN THE CLAIMS:

Please amend claims 1, 2, and 4-8 as follows:

1. (Amended) A plasma processing apparatus for processing an object

to be processed using a plasma, comprising:

A1 a processing chamber defining a processing cavity for containing an object

to be processed and a process gas therein;